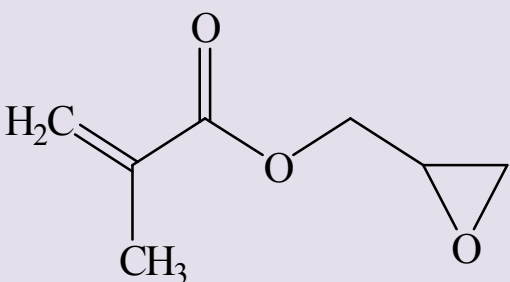
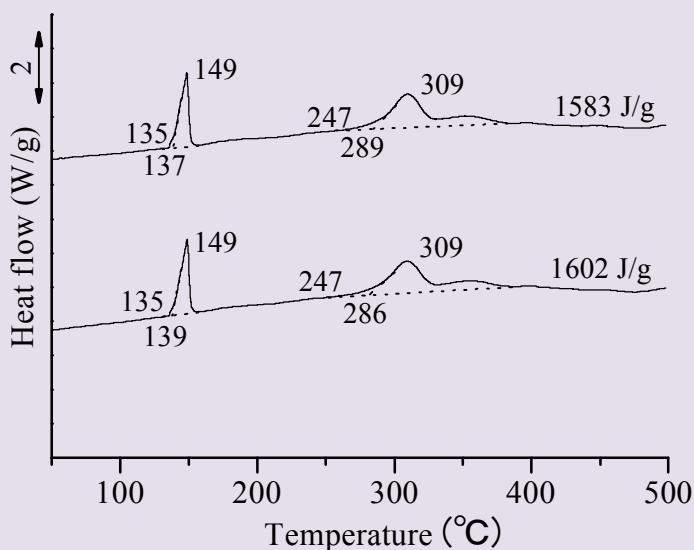


Glycidyl methacrylate	$C_7H_{10}O_3$ GMA
	DSC device: SII DSC 7020 SII Nano Technology Inc. dT/dt: 2, 5, 10, 20 K/min Atmosphere: Air Vesel: pressure vessel (SUS) SII Nano Technology Inc. Sample: Wako (> 95.0%)

a) 2 K/min

Wako: 和光純薬工業株式会社



< Average >

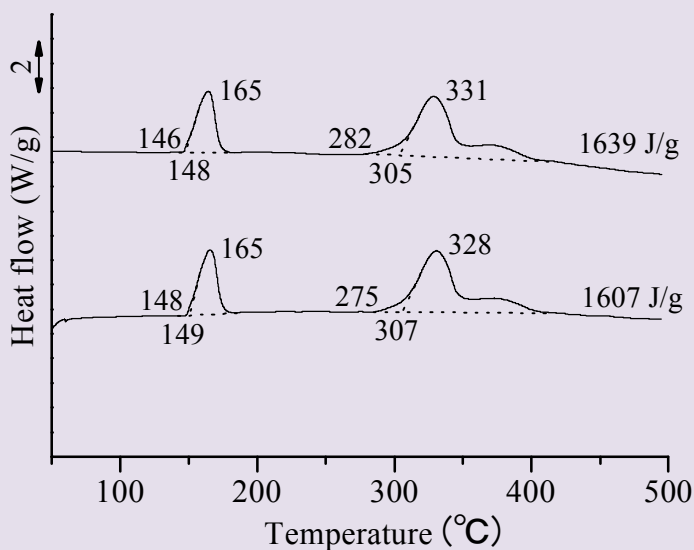
$T_a$ : 247 °C

$T_o$ : 288 °C

$T_{top}$ : 309 °C

$Q_{DSC}$ : 1593 J/g

b) 5 K/min



< Average >

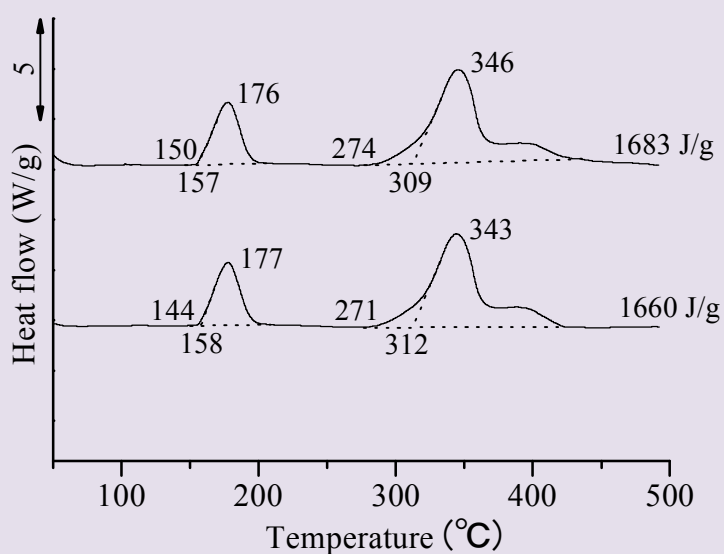
$T_a$ : 279 °C

$T_o$ : 306 °C

$T_{top}$ : 330 °C

$Q_{DSC}$ : 1623 J/g

c) 10 K/min



<Average>

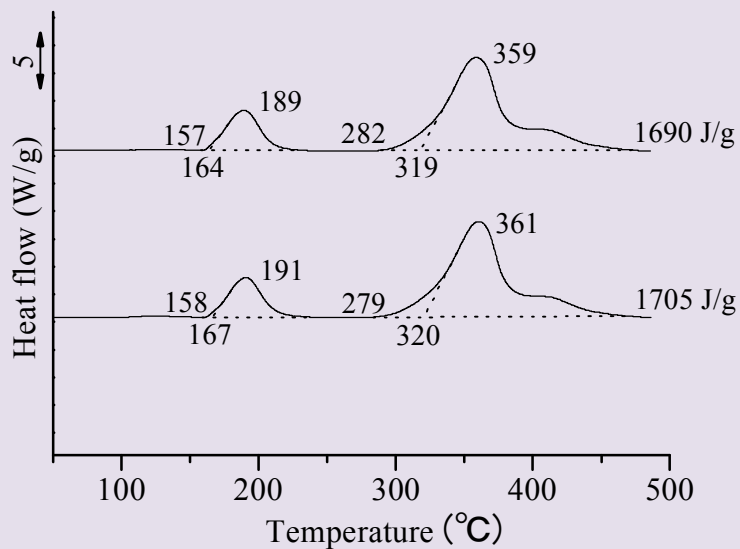
$T_a$  : 273 °C

$T_o$  : 311 °C

$T_{top}$  : 345 °C

$Q_{DSC}$  : 1672 J/g

d) 20 K/min



<Average>

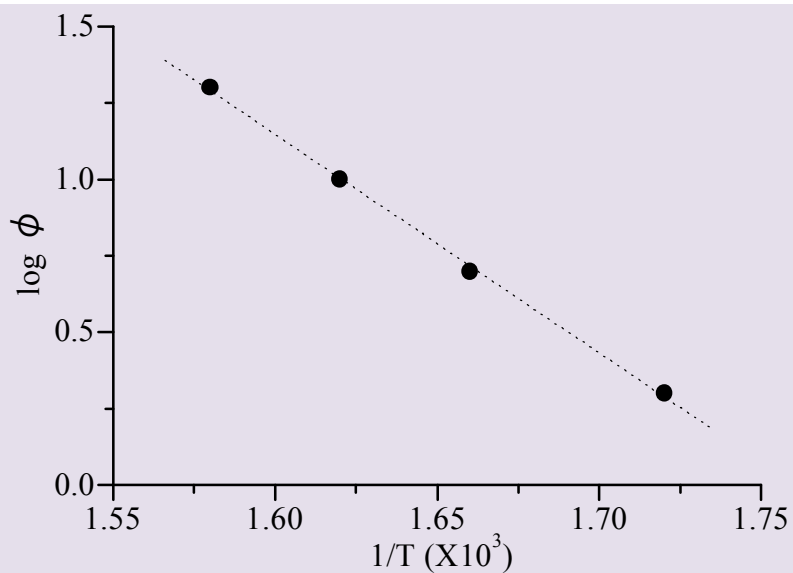
$T_a$  : 281 °C

$T_o$  : 320 °C

$T_{top}$  : 360 °C

$Q_{DSC}$  : 1698 J/g

## ASTM PLOT



Heat rate $\phi$ (K/min)	$T_{\text{peak}}$ (°C)	$T_m$ (K)	$1/T_m \cdot 10^3$	$\log \phi$
2	309	582	1.72	0.301
	309	582	1.72	0.301
5	331	604	1.66	0.699
	328	601	1.66	0.699
10	346	619	1.62	1.00
	343	616	1.62	1.00
20	359	632	1.58	1.30
	361	634	1.58	1.30